

Remarks/Argument

Claim Summary

By this Amendment, claim 9 has been amended, claims 10-11 and 13-16 have been cancelled, and new claims 17-28 are presented for the Examiner's consideration.

Claims 1-9 and 17-28 are now pending in the application.

Allowable Claims

Applicants acknowledge with thanks the indicated allowability of original claims 1-8.

35 U.S.C. §103

By this Amendment, independent claim 9 has been revised to recite that the anneal process utilized to form the silicide layer includes two anneal processes, one of which is executed at a temperature of 650°C or more. See, for example, column 4, lines 56-63, and column 5, lines 53-58, of the reissue specification. Applicants can find no teachings of this aspect of the invention in the references cited by the Examiner, particularly in combination with the remaining features of claim 9. For at least this reason, Applicants respectfully contend that claim 9, and the claims 17-28 dependent thereon, would not have been obvious to one of ordinary skill in view of the Fulford, Jr. et al., Sheng et al., and Tsai et al. references, taken individually or in combination.

Conclusion

No other issues remaining, reconsideration and favorable action upon the claims 1-9 and 17-28 are now pending in the application are requested.

Respectfully submitted,

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